

[ABSTRACT]

The invention addresses the problem that, owing to an increase in the effects of substrate position accuracy on the uniformity of a film formed on a substrate, a situation arises, wherein, even if the substrate has been aligned with the central axis of a boat and inserted into a reaction tube, it cannot be said with certainty that the placement is on the central axis of the reaction tube, and thus, there is a need for the wafer to be placed at an appropriate position on the basis of the actual installed dimensions of the reaction tube, or the like, to improve the uniformity of the processing. To this end, the invention comprises: a boat 21 whereon a plurality of substrates are placed; a processing oven 2 that has a reaction tube 4 into which the boat is inserted and that is for forming a film on each of the substrates placed on the boat; and a substrate transfer machine 125 for introducing each of the substrates into the boat. The substrate transfer machine introduces each of the substrates into the boat by taking a virtual central axis of the reaction tube as the reference.